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SHIGA7.039APC PATENT

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant

Shimbori, H.

Appl. No.

10/561,760

Filed

December 21, 2005

For

RESIN FOR POSITIVE RESIST COMPOSITION, AND POSITIVE RESIST COMPOSITION USING THE SAME, LAMINATE AND

METHOD FOR FORMING

RESIST PATTERN

Examiner

Lee, Sin J.

Group Art Unit

1752

## AMENDMENT AND RESPONSE TO FINAL OFFICE ACTION

## Mail Stop AF

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

OK TO ENTER: /SL/

## Dear Sir:

In response to the final Office Action mailed March 18, 2008, please consider the following amendments and remarks.

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks begin on page 5 of this paper.

OK TO ENTER: /SL/